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U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10026973	12/27/2001	430	5	1756	Rosasco

****APPLICANTS:** Hattori Takashi; Gotoh Yasuko; Satoh Hidetoshi; Tanaka Toshihiko;
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****CONTINUING DATA VERIFIED:**

none

**** FOREIGN APPLICATIONS VERIFIED:**

JAPAN 2000-401154 12/28/2000

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no		ATTORNEY DOCKET NO T&A-109
35 USC 119 conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no		
Verified and Acknowledged Examiners's initials <i>RL</i>		
TITLE : Photomask, the manufacturing method, a patterning method, and a semiconductor device manufacturing method		

U.S. DEPT. OF COMM./PAT & TM-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drawn	Figs. Drawn
		Print Figs.	
<input type="checkbox"/> TERMINAL DISCLAIMER		Application Examiner	
		PREPARED FOR ISSUE	
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